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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.	
10/625,546	07/24/2003	Yutaka Hirose	YMOR:294	8197	
6160	7590 10/20/2005		EXAMINER		
PARKHURST & WENDEL, L.L.P. 1421 PRINCE STREET SUITE 210			PAREKH	PAREKH, NITIN	
			ART UNIT	PAPER NUMBER	
	RIA, VA 22314-2805	2811			
			DATE MAILED: 10/20/2005		

Please find below and/or attached an Office communication concerning this application or proceeding.

		9			
	Application No.	Applicant(s)			
	10/625,546	HIROSE ET AL.			
Office Action Summary	Examiner	Art Unit			
	Nitin Parekh	2811			
The MAILING DATE of this communication app Period for Reply	ears on the cover sheet with the c	orrespondence address			
A SHORTENED STATUTORY PERIOD FOR REPLY IS SET TO EXPIRE 3 MONTH(S) OR THIRTY (30) DAYS, WHICHEVER IS LONGER, FROM THE MAILING DATE OF THIS COMMUNICATION.  - Extensions of time may be available under the provisions of 37 CFR 1.136(a). In no event, however, may a reply be timely filed after SIX (6) MONTHS from the mailing date of this communication.  - If NO period for reply is specified above, the maximum statutory period will apply and will expire SIX (6) MONTHS from the mailing date of this communication.  - Failure to reply within the set or extended period for reply will, by statute, cause the application to become ABANDONED (35 U.S.C. § 133).  Any reply received by the Office later than three months after the mailing date of this communication, even if timely filed, may reduce any earned patent term adjustment. See 37 CFR 1.704(b).					
Status					
1) Responsive to communication(s) filed on <u>04 August 2005</u> .					
2a) ☐ This action is <b>FINAL</b> . 2b) ☐ This action is non-final.					
3) Since this application is in condition for allowance except for formal matters, prosecution as to the merits is					
closed in accordance with the practice under E	x parte Quayle, 1935 C.D. 11, 45	63 O.G. 213.			
Disposition of Claims					
4)  Claim(s) 1-3 is/are pending in the application.  4a) Of the above claim(s) is/are withdraw  5)  Claim(s) is/are allowed.  6)  Claim(s) 1-3 is/are rejected.  7)  Claim(s) is/are objected to.  8)  Claim(s) are subject to restriction and/or					
Application Papers					
9) The specification is objected to by the Examine 10) The drawing(s) filed on 24 July 2003 is/are: a) Applicant may not request that any objection to the Replacement drawing sheet(s) including the correction 11) The oath or declaration is objected to by the Ex	☑ accepted or b) ☐ objected to be drawing(s) be held in abeyance. See ion is required if the drawing(s) is obj	e 37 CFR 1.85(a). ected to. See 37 CFR 1.121(d).			
Priority under 35 U.S.C. § 119					
<ul> <li>12) Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f).</li> <li>a) All b) Some * c) None of:  1. Certified copies of the priority documents have been received.</li> <li>2. Certified copies of the priority documents have been received in Application No</li> <li>3. Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)).</li> <li>* See the attached detailed Office action for a list of the certified copies not received.</li> </ul>					
Attachment(s)					
1) Notice of References Cited (PTO-892) 2) Notice of Draftsperson's Patent Drawing Review (PTO-948)	4)  Interview Summary Paper No(s)/Mail Da				

U.S. Patent and Trademark Office PTOL-326 (Rev. 7-05)

Paper No(s)/Mail Date \_

3) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08)

6) Other: \_\_\_\_.

5) Notice of Informal Patent Application (PTO-152)

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## **DETAILED ACTION**

## Claim Rejections - 35 USC § 103

1. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

2. Claims 1-3 are rejected under 35 U.S.C. 103(a) as being unpatentable over Herner et al. (US Pat. 2003/0030147) in view of Nakamura et al. (US Pat. 6204512).

Regarding claims 1-3, Herner et al. disclose a contact/an ohmic contact formation method comprising:

- forming a composite film comprising silicon (Si) and titanium (Ti) on a surface layer of a semiconductor region (see 28 and 30 respectively on the region 12 in Fig. 3; sections 0021-0023) of a semiconductor material including a Group III nitride semiconductor (see section 0039)
- the Si and Ti films being formed in the order of depositing Si followed by Ti (sections 0022, 0023 and 0028), and
- heat treating/annealing the films and the semiconductor layer at a temperature of about 800 deg. C (section 0025)

(Fig. 2-5; sections 0022-0039; pp. 1-4).

Herner et al. further disclose semiconductor material layer comprising GaAs, GaN, etc. having n-type diffusing dopant in the formation of the ohmic contacts (see sections 0039 and 0040), but fail to teach the semiconductor material layer having diffusing Si as a dopant.

Nakamura et al. teach forming ohmic contacts using semiconductor material layer such as n-type GaN (see 12 in Fig. 6) having conventional Si as a dopant (Col. 5, lines 17-24; Col. 11, lines 24-30).

It would have been obvious to a person of ordinary skill in the art at the time invention was made to incorporate teach the semiconductor material layer having diffusing Si as a dopant as taught by Nakamura et al. so that the desired ohmic characteristics and electrical performance can be achieved in Herner et al's ohmic contact.

## Response to Arguments

- 4. Applicant's arguments filed on 08-04-05 have been fully considered but they are not persuasive.
- A. Applicant contends that Fig. 3 of Herner et al. shows a layer of Ti and a layer of Si on a polysilicon layer, not a layer of a Group III nitride semiconductor.

However, as explained in the rejections above, Herner et al. clearly disclose other semiconductor material including group III nitride/GaN (see section 0039).

5. **THIS ACTION IS MADE FINAL.** Applicant is reminded of the extension of time policy as set forth in 37 CFR 1.136(a).

A shortened statutory period for reply to this final action is set to expire THREE MONTHS from the mailing date of this action. In the event a first reply is filed within TWO MONTHS of the mailing date of this final action and the advisory action is not mailed until after the end of the THREE-MONTH shortened statutory period, then the shortened statutory period will expire on the date the advisory action is mailed, and any extension fee pursuant to 37 CFR 1.136(a) will be calculated from the mailing date of the advisory action. In no event, however, will the statutory period for reply expire later than SIX MONTHS from the mailing date of this final action.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Nitin Parekh whose telephone number is 571-272-1663. The examiner can normally be reached on 09:00AM-05:30PM.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's acting supervisor, Steven Loke can be reached on 571-272-1657.

The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

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Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAN or Public PAG. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAG system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free). Any inquiry of a general nature or relating to the status of this application or proceeding should be directed to the receptionist whose telephone number is 703-308-0956.

NP

10-16-05

NITIN PAREKH

Nitri Pareth

PRIMARY EXAMINER

**TECHNOLOGY CENTER 2800**